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CONVENIENT SYNTHESIS OF S-TRIMETHYLSILYL ESTERS OF DITHIO- AND TETRATHIOPHOSPHORIC ACIDS

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CONVENIENT SYNTHESIS OF *S*-TRIMETHYLSILYL ESTERS OF DITHIO- AND TETRATHIOPHOSPHORIC ACIDS

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S-Trimethylsilyl esters of dithio- and tetrathiophosphoric acids were obtained in the reaction of tetraphosphorus decasulfide with alkoxy- and alkylthiotrimethylsilanes, trimethylsilyl enol ethers and bis(trimethylsiloxy)alkylenes and phenylene.

Key words: *S*-Trimethylsilyl esters of dithio- and tetrathiophosphoric acids; tetraphosphorus decasulfide; alkoxy- and alkylthiotrimethylsilanes; trimethylsilyl enol ethers; bis(trimethylsiloxy)alkylenes.

INTRODUCTION

S-Trimethylsilyl dithiophosphates are important intermediates for the synthesizing useful organothiophosphorus compounds.¹ They are also efficient thiation reagents for ketones and isocyanates.¹ There are several methods for the preparation of *S*-trimethylsilyl dithiophosphates with dialkyl and 1,2-dioxyalkylene or arylene substituents. They were obtained by the interaction of dithiophosphoric acids with 1,1,1,3,3,3-hexamethyldisilazane² or trimethylisocyanatosilane, or its thioanalogue, or trimethylsilyl enol ethers.³ Reactions of ammonium dialkyl dithiophosphates with trimethylchlorosilane also result in *S*-trimethylsilyl dithiophosphates.⁴ However, these techniques are multi-step procedures as the initial dithiophosphoric acids had been synthesized by treatment of organic hydroxy compounds with phosphorus sulfide (P₄S₁₀) with evolution of gaseous hydrogen sulfide.⁵ The shortcomings of these syntheses also involve heating of the reaction mixture (60–70°C) and formation of by-products.

On the other hand, *S*-trimethylsilyl dithiophosphates with unsaturated substituents and dialkyl(trimethylsilyl)tetrathiophosphates remained unknown.

Tetraphosphorus decasulfide **1** is known to react with trimethyl(dialkyl-amino)silanes and bis(trimethylsilyl)sulfide to form *S*-trimethylsilyl *N,N'*-bis(dialkylamido)dithiophosphates and tris(trimethylsilyl)tetrathiophosphates respectively.⁶ We have tried to extend these degradation reactions of **1** to other organosilicon compounds. In this article convenient and efficient methods are presented for the synthesis of *S*-trimethylsilyl esters of dithio- and tetrathiophosphoric acids directly from **1**.

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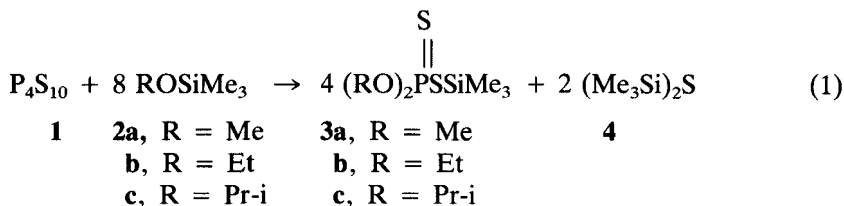
TABLE I
Experimental, physical and analytical data of the products obtained

Initial cpd.	Prod.	Reaction conditions temp. (°C)/time (h)	Yield ^a (%)	B. p. °C (mm Hg)	d ₄ ²⁰	n _D ²⁰	³¹ P NMR ^f δ, ppm	Molecular formula	Analytical data Found/Calc. (%)					[M + H] ⁺ Found/Calc.	
									C	H	P	S	Si		
2a	3a	40–50/6.5	77	55–58 (0.02) ^d		1.5287	93	C ₃ H ₁₅ O ₂ PS ₂ Si	25.96	6.91	13.69	27.58	12.25	231	
2b	3b	40/10	81	59–60 (0.02) ^e		1.5141	89	C ₉ H ₁₉ O ₂ PS ₂ Si	26.08	6.59	13.46	27.80	12.16	231	
2c	3c	20/12	78	66–67 (0.03)	0.9902	1.4782	86	C ₉ H ₂₃ O ₂ PS ₂ Si	32.17	7.20	12.41	25.01	10.82		
									32.55	7.44	12.00	24.78	10.84		
6a	5a	40–50/10	80	110–117 (0.02) ^b	1.0525	1.5090	89	C ₉ H ₁₉ O ₂ PS ₂ Si	37.63	8.09	10.54	22.88	9.08		
									37.73	8.12	10.82	22.35	9.78		
6b	5b	70–90/8	67	120–128 (0.02) ^b	1.1606	1.5433	93	C ₉ H ₁₉ O ₂ PS ₂ Si	37.94	6.48	10.66	22.51	10.19	283	
									38.29	6.80	10.98	22.67	9.92	283	
6c	5c	40–50/9	85	140–160 (0.03) ^b	1.0732	1.5500	60	C ₁₅ H ₂₇ O ₂ PS ₂ Si	38.84	5.14	11.08	23.25	10.13	279	
									38.84	5.45	11.14	23.00	10.06	279	
6d	5d	50–60/4	91 ^c			1.5622	59	C ₁₃ H ₂₃ O ₂ PS ₂ Si	49.51	7.67	8.43	17.82	7.43	363	
									49.70	7.53	8.55	17.66	7.72	363	
7a	8a	20/12	85	90–100 (0.02) ^b	1.1067	1.5885	83	C ₇ H ₁₉ PS ₂ Si	46.78	6.58	9.20	19.36	8.22		
									46.69	6.95	9.27	19.14	8.37		
7b	8b	20/3	95	110–115 (0.02) ^b	1.0628	1.5650	83	C ₉ H ₂₃ PS ₂ Si	28.84	6.74	10.62	43.89	9.58	291	
									28.96	6.62	10.68	44.09	9.65	291	
7c	8c	50/7	96	120–130 (0.02) ^b	1.0377	1.5635	83	C ₁₁ H ₂₇ PS ₂ Si	33.38	7.64	9.60	40.03	8.66	319	
									33.96	7.30	9.74	40.21	8.80	319	
10a	9a	15–20/7	93 ^c		1.1856	1.5160	81	C ₆ H ₁₅ O ₂ PS ₂ Si	38.32	7.71	8.80	37.28	8.26		
									38.14	7.88	8.95	36.95	8.08		
10b	9b	20–25/10	84	110–115 (0.03) ^b	1.0684	1.4966	99	C ₇ H ₁₆ O ₂ PS ₂ Si	29.30	6.08	12.49	26.89	15.20	243	
									29.75	6.25	12.79	26.41	15.56	243	
10c	9c	190–200/2	34	205–208 ^g			67.9 ^h	C ₉ H ₁₃ O ₂ PS ₂ Si	33.19	6.58	12.47	25.27	10.69		
									32.93	6.34	12.14	25.08	10.97		
									39.25	4.91	11.36	23.36	10.46		
									39.13	4.76	11.22	23.16	10.14		

^aYield of isolated product.^bTemperature of the spiral of the thermal element of the thin layer distillation apparatus.^cYield of crude product.^dLit.⁴ b.p. 44–46 (0.02).^eLit.⁴ b.p. 55–56 (0.001).^fNeat.^gM. p.^hIn PhNO₂.

RESULTS AND DISCUSSION

We assumed that the use of the trimethylsilyl protecting group in protonodonating reagents such as alcohols, enols, thiols and diols may lead to *S*-trimethylsilyldithio- and tetrathiophosphates directly from **1** and thus avoid the formation of hydrogen sulfide. In fact we have found that **1** reacts with alkoxytrimethylsilanes **2a–c** at 20–50°C for 6.5–12 h with the formation of *O,O*-dialkyl-*S*-trimethylsilyl dithiophosphates **3a–c** and bis(trimethylsilyl)sulfide **4** (Equation 1, and Table I).

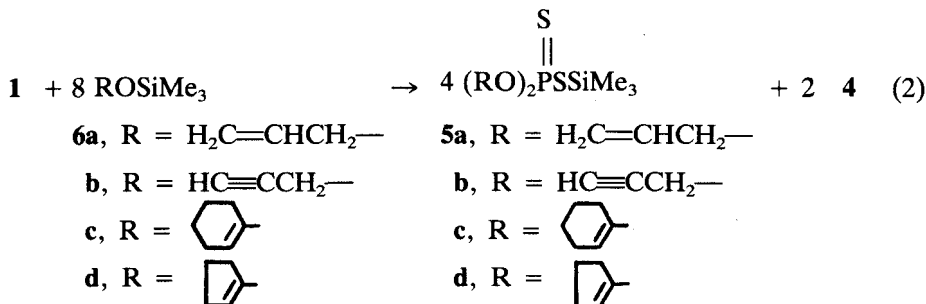


The structures of the products **3a–c** have been established by IR (Table II), ¹H NMR (Table III), ³¹P NMR spectroscopy and by mass spectral data and microanalyses and by comparison of physical constants of the products (**3a,b**⁴) with literature data.

The dithiophosphates **3a–c** prepared with this method were not decomposed during distillation. Unlike this, *S*-trimethylsilyl *N,N'*-bis(dialkylamido)dithiophosphates decomposed during distillation to form bis(*N,N,N',N'*-tetraalkyldiamidothiophosphoryl)sulfide and **4**.⁶

It should be noted that this preparative method (Equation 1) is characterized by minimum steps, simple operation, mild conditions, high yields of products, no solvents and by-products.

We have tried to find the boundary of this method. Although unsaturated dithiophosphoric acids and their metallic salts were prepared^{7–10} the corresponding *S*-silyl esters of unsaturated dithiophosphoric acid were not obtained. We assumed that these compounds may be prepared from trimethylsilyl enol ethers and **1**. Actually *S*-trimethylsilyl diallyl- and dipropargyldithiophosphates **5a,b** were synthesized in the reaction of trimethylallyloxysilane **6a** and trimethyl(2-propyneoxy)silane **6b** with **1** at 40–90°C for 8–9 h (Equation 2, Tables I–III).



Similarly trimethylsilyl cycloalkenylol ethers **6c,d** yield the corresponding *S*-trimethylsilyl esters of dithiophosphoric acid with cycloalkenyl substituents **5c,d** at

TABLE II
IR spectral data (cm^{-1}) of the products obtained

Prod.	CH_3 as, s; CH_2 as, s	$\delta[\text{CH}_3(\text{Si})\text{s}]$	$\text{PO}-\text{C}^a$	$\text{P}-\text{O}-\text{Si}^a$ as	$\rho[\text{CH}_3(\text{Si})]$	$\text{P}=\text{S}^a$	$\text{P}-\text{S}^a, \text{S}-\text{Si}^a$
3a	2950, 2900, 2845	1258	1030		850	665	535, 496
3b	2990, 2970, 2945, 2910, 2875	1258	1025		855	663	546, 514
3c	2975, 2960, 2930, 2897, 2870	1252	1050	968	848	654	546, 513
5a^d	2965, 2880	1260	1020	930	860	685	
5b^e	2965, 2930, 2900, 2875	1260	1020	950	855	680	560
5c^d	2940, 2860, 2840	1258	1020		850	731	
5d^d	2962, 2910, 2875, 2850	1258	1040	950	850	710	570
8a	2964, 2928, 2895, 2870	1252			846	680	546, 516
8b	2968, 2932, 2900, 2875	1255			855	668	548, 523
8c^e	2960, 2930, 2900, 2874	1252			851	684	550, 525
9a	2975, 2908	1258	1060		850	693	
9b	2981, 2960, 2940, 2905	1258	1050	950	850	710	585, 537
9c^{b,d}		1261			862, 840	676	540, 525

^aValence vibrations.

^bIn vaseline oil.

^cDeformation vibrations δ 1384, 1374–1370 cm^{-1} (CH_3)₂C gem.

^d ν 3090–3080, 3055–3028 ($\text{:C}=\text{H}^a$), 1645–1600 cm^{-1} ($\text{C}=\text{C}^a$).

^e ν 3299 ($\text{:C}=\text{H}^a$), 2140 cm^{-1} ($\text{C}\equiv\text{C}^a$).

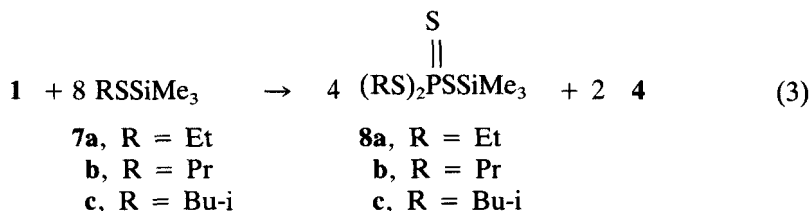
TABLE III
¹H NMR spectral data of the products obtained

Prod.	δ, ppm, J, Hz
3a	0.53 (s, 9H, CH ₃ Si), 3.75 (d, ³ J _{P-H} 15.0) CH ₃ OP).
3b	0.43 (s, 9H, CH ₃ Si), 1.27 (t, 6H, ³ J _{H-H} 7.0, CH ₃ C), 4.02 (dq, 4H, ³ J _{H-H} 7.0, ³ J _{P-H} 10.0, CH ₂ OP).
3c	0.47 (s, 9H, CH ₃ Si), 1.33 (d, 12H, ³ J _{H-H} 6.0, CH ₃ C), 4.75 (dq, 2H, ³ J _{H-H} 6.0, ³ J _{P-H} 18.0, CHOP).
5a	0.45 (s, 9H, CH ₃ Si), 4.47 (dd, 4H, ³ J _{H-H} 5.5, ³ J _{P-H} 10.0, CH ₂ OP), 4.97–5.38 (m, 2H, CH ₂ =CH—CH ₂), 5.39–6.07 (m, 1H, CHCOP).
5b	0.37 (s, 9H, CH ₃ Si), 2.53 (t, 1H, ⁴ J _{H-H} 1.2, CH≡C—CH ₂), 4.60 (dd, ⁴ J _{H-H} 1.2, ³ J _{P-H} 11.0, CH ₂ OP).
5c	0.32 (s, 9H, CH ₃ Si), 1.23–2.44 (m, 16H, CH ₂ cycle), 5.88–6.12 (m, 2H, CH=COP).
5d	0.32 (s, 9H, CH ₃ Si), 1.50–2.97 (m, 12H, CH ₂ cycle), 5.67–5.90 (m, 2H, CH=C—OP).
8a	0.54 (s, 9H, CH ₃ Si), 1.35 (t, 6H, ³ J _{H-H} 7.5, CH ₃ C), 2.92 (dq, 4H, ³ J _{H-H} 7.5, ³ J _{P-H} 17.0, CH ₂ SP).
8b	0.80 (s, 9H, CH ₃ Si), 1.27 (t, 6H, ³ J _{H-H} 6.5, CH ₃ C), 1.70–2.25 (m, 4H, ³ J _{H-H} 6.5, CH ₂ CC), 3.07 (dq, 4H, ³ J _{H-H} 6.5, ³ J _{P-H} 16.0, CH ₂ SP).
8c	0.52 (s, 9H, CH ₃ Si), 1.00 (d, 12H, ³ J _{H-H} 6.0, CH ₃ CC), 1.72–2.22 (m, 2H, CHCS), 2.76 (dd, 4H, ³ J _{P-H} 15.0, CH ₂ SP).
9a ⁺	0.38 (s, 9H, CH ₃ Si), 1.68–2.31 (m, CH ₂ H ₂ COP), 3.84–5.61 (m, 4H, CH _{BB} ·H _{AA} ·OP).
9b ⁺	0.50 (s, 9H, CH ₃ Si), 1.35–1.50 (m, 6H, CH ₃ COP), 4.02–4.38 (m, 2H, CHOP).
9c	0.17 (s, 9H, CH ₃ Si), 6.96–7.07 (m, 4H, C ₆ H ₅).

⁺The mixture of cis and trans isomers.

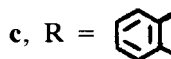
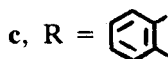
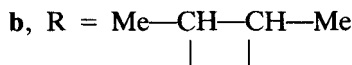
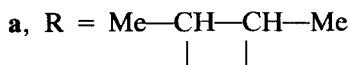
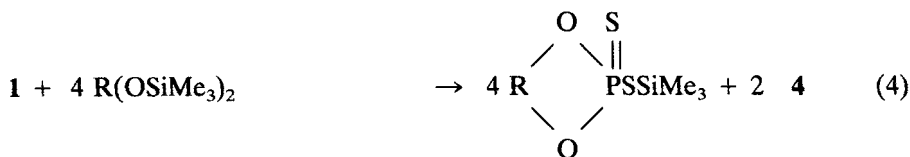
40–60°C for 4–9 h (Equation 2, Tables I–III). However these reactions (Equation 2) proceed at higher temperature (40–90°C) and **5d** decomposed when distillation was attempted.

Tris(trimethylsilyl) tetrathiphosphate was described.⁶ In spite of the existence of metal and ammonium dialkyl tetrathiphosphates^{11–13} the corresponding *S*-silyl esters of dialkyl tetrathiphosphoric acid remained unknown. We have found that the interaction of alkylthiotrimethylsilanes **7a–c** with **1** gives dialkyl(trimethylsilyl)tetrathiphosphates **8a–c** and **4** at 20–50°C for 3–12 h (Equation 3, Tables I–III).



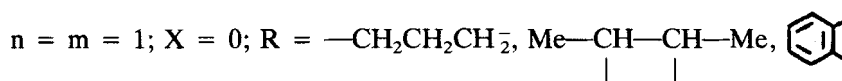
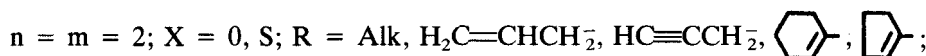
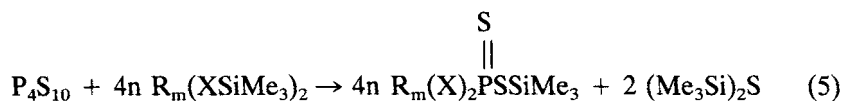
Tetrathiphosphates **8a–c** are stable compounds and were isolated from the reaction mixture by distillation pure (thin layer distillation). It is noteworthy that the reaction of **1** with **7a** proceeds more readily than that with **2b**.

Our approach enabled us to obtain *S*-trimethylsilyl derivatives of cyclic dithiophosphoric acid with 1,2-dioxyalkylene and arylene substituents **9a–c** with the help of the ring-closure reaction of **1** with bis(trimethylsiloxy)alkylenes **10a,b** and phenylene **10c** (Equation 4, Tables I–III).



It is remarkable that the reactivity of benzene **10c** (reaction conditions: 190–200°C, 2 h) is lower than that of alkylene derivatives **10a,b** (15–25°C, 7–10 h) and the yield of **9c** is not high (34%) (Table I). Ester **9a** is thermally unstable and decomposes on distillation. The stability of the cyclic products **9** is increased when sterically hindered substituents at the phosphorus atom are introduced (**9b** is more stable than **9a**). Esters **9** decompose when stored for a long time in sealed tubes at room temperature.

Thus a general scheme can be conceived on the basis of the results of the following reactions of **1** with alkoxytrimethylsilanes, trimethylallyloxysilane, trimethyl(2-propynoxy)silane, trimethylsilyl cycloalkenyl ethers, alkylthiotrimethylsilanes and bis(trimethylsiloxy)alkylenes and phenylene (Equation 5).



The mechanism of the degradation of **1** with silylamines has been discussed by Roesky and Remmers⁶ when the nucleophilic nitrogen atom attacks the phosphorus atom of **1**. Perhaps the mechanisms of formation of **3**, **5**, **8** and **9** are similar to those suggested by Roesky and Remmers.⁶

In all cases the reactions (Equations 1–4) were accompanied by the formation of **4**, which is easily given off from the reaction mixture. It may be utilized by treating it with **1** or 2,4-bis(4-phenyl)-2,4-dithioxo-1,3,2λ⁵,4λ⁵-dithiadiphosphetane to yield organosilylthiophosphorus compounds,⁶ which are useful as intermediates in organophosphorus synthesis.

The toxicity measurements of products obtained were performed and the minimal toxicity dose (in vitro) was 15.6 for **6a**, 15.6 for **8a**, 7.8 for **8b** and 500 mg/mL for **8c**.

EXPERIMENTAL

The initial compounds **2**, **6**, **7** and **10** were prepared according to Reference 14. ^{31}P NMR spectra were recorded with a Bruker WM 250 (101.3 MHz) and a non-serial NMR KGU-4 (10.2 MHz) spectrometer, reference external H_3PO_4 (85%). ^1H NMR spectra were run on a Varian T-60 (60 MHz) spectrometer in CCl_4 with C_6H_6 as an internal reference and on a Bruker WM 250 (250 MHz) spectrometer in CD_3CN . IR spectra were obtained in KBr with a UR-20 and Specord M 80 infrared spectrophotometer. Mass spectra (electron impact, 70 eV; chemical ionization, 100 eV) were determined on a M 80 B Hitachi chromatograph mass spectrometer.

Dipropyl-S-trimethylsilyl tetrathiophosphate 8b; Typical Procedure. **1** (20.4 g, 46 mmol) is added portionwise to a stirred **7b** (54.6 g, 368 mmol) at 20°C under an argon atmosphere and stirring is continued for 3 h at 20°C . The mixture is evaporated at reduced pressure (10 and 0.03 mm Hg) at 40°C . **8b** (55.6 g, 95%) is isolated from the residue by means of thin layer distillation (see Tables I–III). **4** is distilled from the reaction mixture; the yield is 7.9 g (98%); b.p. 159°C (733 mm Hg); n_D^{20} 1.4591 (Lit.¹³ b.p. 162.5 – 163.5°C (750 mm Hg); n_D^{20} 1.4598).

The products **3a–c**, **5a–d**, **8a** and **8c** are obtained similarly. Products **3a–c** are in addition purified by distillation after the isolation by means of thin layer distillation. Products **9a,b** are prepared by the reaction of **1** with **10a,b** in the molar ratio 1:4 and isolated similarly. Products **5d** and **9a** are not purified by the following distillation.

2-Trimethylsilylthio-2-thio-4,5-benzene-1,3,2-dioxaphospholane 9c. The mixture of **1** (10.0 g, 22.5 mmol) and **10c** (23.0 g, 90.4 mmol) is stirred for 2 h at 190 – 200°C under an argon atmosphere. The precipitate is filtered, washed with anhydrous hexane and dried at reduced pressure (0.02 mm Hg) at 40°C . Yield of **9c**: 8.5 g (34%) (see Tables I–III).

"The toxicity measurements of the products obtained were performed and the minimal toxicity dose (in vitro) was: 15.6 for **6a**, 15.6 for **8a**, 7.8 for **8b** and 500 mg/mL for **8c**.

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